Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	318	(PE-CVD OR PECVD OR (("plasma-enhanced" or "plasma enhanced") AND (CVD or "chemical vapor deposition"))).clm. same (reactor or vessel or system).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/06 19:40
S2	227	S1 AND (coat\$3 or film\$3) and (part or component)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 18:37
S3	23	S1 AND (coat\$3 or film\$3) and (liner)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 18:37
S4	725	(PE-CVD OR PECVD OR (("plasma-enhanced" or "plasma enhanced") AND (CVD or "chemical vapor deposition"))).clm. same (reactor or vessel or chamber or system).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 18:39
S5	970	(PE-CVD OR PECVD OR PVD or PCVD or (("plasma-enhanced" or "plasma enhanced") AND (CVD or "chemical vapor deposition"))).clm. same (reactor or vessel or chamber or system).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND .	ON	2007/03/20 18:42
S6	57	S5 AND ((coat\$3 or film or layer) near3 (liner or component or part)). clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 18:42
S7	1114	(PE-CVD OR PECVD OR PVD or PCVD or (("plasma-enhanced" or "plasma enhanced") AND (CVD or "chemical vapor deposition"))).clm. same (reactor or vessel or chamber or system or apparatus).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 18:42
S8	65	S7 AND ((coat\$3 or film or layer) near3 (liner or component or part)). clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 18:48
S9	3531	COATED (PE-CVD OR "PLASMA PROCESSING") (REACTOR OR CHAMBER OR VESSEL OR APPARATUS)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 18:50
S10	356	COATED SAME (PE-CVD OR "PLASMA PROCESSING") SAME (REACTOR OR CHAMBER OR VESSEL OR APPARATUS)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 19:26

S11	7345	(COAT\$3 or condition\$3 or pre-condition\$3 or pre-condition\$3 or treat\$2 or pretreat\$2 or pre-treat\$2) SAME (PE-CVD or PCVD OR PVD OR PECVD OR "PLASMA-ENHANCED" OR "PLASMA PROCESSING") SAME (REACTOR OR CHAMBER OR VESSEL OR APPARATUS OR SYSTEM)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 13:48	
S12	468	((COAT\$3 or condition\$3 or pre-condition\$3 or pre-condition\$3 or treat\$2 or pretreat\$2 or pre-treat\$2) SAME (PE-CVD or PCVD OR PVD OR PECVD OR "PLASMA-ENHANCED" OR "PLASMA PROCESSING") SAME (REACTOR OR CHAMBER OR VESSEL OR APPARATUS OR SYSTEM)).CLM.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/20 19:29	
S13	386	((COAT\$3 or condition\$3 or pre-condition\$3 or pre-condition\$3 or treat\$2 or pretreat\$2 or pre-treat\$2) SAME (PE-CVD or PCVD OR PECVD OR "PLASMA-ENHANCED" OR "PLASMA PROCESSING") SAME (REACTOR OR CHAMBER OR VESSEL OR APPARATUS OR SYSTEM)).CLM.	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/03/21 13:18	
S23	26	plasma with (pump\$ with excess with (gas or vapor))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 14:10	
S24	1	pump\$3 near3 (deposit\$3 adj shield)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 14:12	
S25	18	(pump\$3 near3 shield) with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 14:26	
S26	69	(pump\$3 with shield) with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 14:26	
S27	28	((vapor\$ or gas\$4) adj (deposit\$3 or epitax\$3)) and ((pump\$3 with shield) with plasma)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 14:27	
S28	4	(chamber or apparatus) with component with coat\$3 with \$4season\$3 with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 16:02	

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S29	24	(chamber or apparatus) with coat\$3 with \$4season\$3 with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 16:07
S30	203	(chamber or apparatus) with \$4season\$3 with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 16:45
S31	196	(chamber or apparatus) with (\$4season\$3 or \$4condition\$3) with plasma with ((silicon adj (oxide or dioxide)) or SiO2 or "SiO.sub.2" or silica)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 18:13
S32	85	(chamber or apparatus) with (part or component or surface or liner or piece or workpiece) with (\$4coat\$3 or \$4conditioning or \$4conditioned) with plasma with ((silicon adj (oxide or dioxide)) or SiO2 or "SiO.sub.2" or silica)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 20:16
S33	4949	(chamber or apparatus) with (part or component or surface or liner or piece or workpiece) with (\$4coat\$3 or \$4conditioning or \$4conditioned) with (dispos\$3 or install\$5 or use)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 20:19
S34	. 195	(chamber or apparatus) with (part or component or surface or liner or piece or workpiece) with (\$4coat\$3 or \$4conditioning or \$4conditioned) with (dispos\$3 or install\$5 or use) with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 20:29
S36	183	(chamber or apparatus) with (part or component or surface or liner or piece or workpiece) with (\$4coat\$3 or \$4conditioning or \$4conditioned) with (dispos\$3 or install\$5 or reinstall\$5) with plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 20:41
S38	382	(apparatus near3 (assembl\$3)) with (part or component or surface or liner or piece or workpiece) with (\$4coat\$3 or \$4conditioning or \$4conditioned)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 20:42
S39	18	(apparatus near3 (assembl\$3)) with (part or component or surface or liner or piece or workpiece) with (\$4coat\$3 or \$4conditioning or \$4conditioned) same (plasma or PECVD OR "PE-CVD")	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 20:47

S40	35	((plasma or PECVD OR "PE-CVD") ADJ APPARATUS) AND ((ASSEMBLE OR ASSEMBLED) WITH (PART OR COMPONENT))	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/05 20:48
S42	0	PECVD WITH (PROCESS OR METHOD) WITH CHUCK WITH (COAT\$3 OR FILM)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/06 23:24
S43	24	(PECVD OR "PE-CVD" OR (PLASMA NEAR3 (VAPOR ADJ DEPOSIT\$3))) WITH (PROCESS OR METHOD) WITH CHUCK WITH (COAT\$3 OR FILM)	US-PGPUB; USPAT; EPO; JPO; DERWENT	AND	ON	2007/06/06 19:44